

1 1. ~~A reflector comprising:~~  
2 a reflective layer; and  
3 an absorbing layer that preferentially absorbs  
4 blue light, said absorbing layer being located over said  
5 reflective layer.

1 2. The reflector of claim 1 wherein said reflector  
2 is a micromirror.

1 3. The reflector of claim 1 wherein said reflective  
2 layer is formed of silver, said silver being formed over a  
3 polished semiconductor material.

1 4. The reflector of claim 3 wherein said silver  
2 layer is covered by an insulator.

1 5. The reflector of claim 3 wherein the absorbing  
2 layer includes silicon nitride.

1 6. The reflector of claim 4 wherein said absorbing  
2 layer includes silicon dioxide.

1 7. The reflector of claim 4 wherein said insulator  
2 includes about 700 to 750 Angstroms of silicon dioxide and  
3 about 700 to about 750 Angstroms of silicon nitride.

1 8. A method comprising:  
2 forming a reflective layer; and  
3 forming an absorbing layer over said reflective  
4 layer that absorbs a particular wavelength of light.

1 9. The method of claim 8 including forming a  
2 reflective layer by depositing silver on a semiconductor  
3 layer.

1 10. The method of claim 8 including forming an  
2 absorbing layer including a layer of two different  
3 insulator materials.

1 11. The method of claim 9 including forming said  
2 silver layer at a temperature of 50°C or less.

1 12. The method of claim 10 including forming said  
2 absorbing layer at a temperature of less than 250°C.

1 13. The method of claim 12 including forming said  
2 absorbing layer using chemical vapor deposition.

1 14. The method of claim 8 including forming said  
2 absorbing layer of a layer of oxide and a layer of nitride.

1 15. The method of claim 14 including forming said  
2 oxide and nitride layers of a thickness of about 700 to  
3 about 750 Angstroms.

1 16. A reflector comprising:  
2 a silicon substrate; and  
3 a silver layer formed directly on said silicon  
4 substrate.

1 17. The reflector of claim 16 wherein said reflector  
2 is a micromirror.

1 18. The reflector of claim 16 including an absorbing  
2 layer over said silver layer.

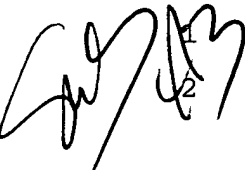
1 19. The reflector of claim 18 wherein said absorbing  
2 layer preferentially absorbs blue light.

1 20. The reflector of claim 18 wherein said absorbing  
2 layer includes silicon nitride.

1 21. The reflector of claim 20 wherein said absorbing  
2 layer includes silicon dioxide.

1           22. The reflector of claim 21 wherein said insulator  
2 includes about 700 to 750 Angstroms of silicon dioxide and  
3 from about 700 to about 750 Angstroms of silicon nitride.

1           23. The reflector of claim 16 wherein said silver  
2 layer is formed at a temperature below 50°C.

 1           24. The reflector of claim 18 wherein said insulator  
2 is formed at a temperature below 250°C.

1           25. A method comprising:  
2                 depositing silver on a silicon substrate at a  
3 temperature less than 50°C; and  
4                 forming an absorbing layer over said silver.

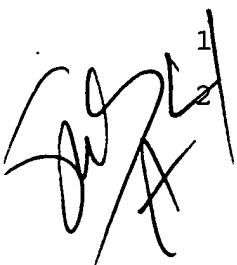
1           26. The method of claim 25 including forming an  
2 absorbing layer including a layer of two different  
3 insulator materials.

1           27. The method of claim 26 including forming said  
2 absorbing layer at a temperature of less than 250°C.

1           28. The method of claim 26 including forming said  
2 absorbing layer of a layer of oxide and a layer of nitride.

1           29. The method of claim 28 including forming said  
2 oxide and nitride layers of a thickness of about 700 to  
3 about 750 Angstroms.

1           30. The method of claim 25 including depositing  
2 silver using chemical vapor deposition.

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